

Title (en)

REMOTE CHAMBER METHODS FOR REMOVING SURFACE DEPOSITS

Title (de)

VERFAHREN MIT ENTFERNT ANGEORDNETER KAMMER ZUR ENTFERUNG VON OBERFLÄCHENABLAGERUNGEN

Title (fr)

PROCEDES D'ELIMINATION DE DEPOTS DE SURFACE PAR ENCEINTE A DISTANCE

Publication

**EP 1733071 A2 20061220 (EN)**

Application

**EP 05734780 A 20050324**

Priority

- US 2005010691 W 20050324
- US 55622704 P 20040324
- US 64083304 P 20041230
- US 64044404 P 20041230

Abstract (en)

[origin: WO2005090638A2] The present invention relates to an improved remote plasma cleaning method for removing surface deposits from a surface, such as the interior of a deposition chamber that is used in fabricating electronic devices. The improvement involves addition of a nitrogen source to the feeding gas mixture comprising of oxygen and fluorocarbon. The improvement also involves pretreatment of interior surface of the pathway from the remote chamber to the surface deposits by activating a pretreatment gas mixture comprising of nitrogen source and passing the activated pretreatment gas through the pathway.

IPC 8 full level

**B08B 7/00** (2006.01); **C23C 16/44** (2006.01); **C23F 4/00** (2006.01); **H01J 37/32** (2006.01); **H01L 21/00** (2006.01)

CPC (source: EP KR)

**B08B 7/0035** (2013.01 - EP); **C23C 16/44** (2013.01 - KR); **C23C 16/4405** (2013.01 - EP); **C23F 4/00** (2013.01 - KR); **H01J 37/32862** (2013.01 - EP); **H01L 21/00** (2013.01 - KR); **Y02C 20/30** (2013.01 - EP)

Citation (search report)

See references of WO 2005095670A2

Designated contracting state (EPC)

DE FR GB IE IT NL

DOCDB simple family (publication)

**WO 2005090638 A2 20050929; WO 2005090638 A3 20060413; WO 2005090638 A8 20061116; WO 2005090638 A9 20060126;**  
BR PI0508204 A 20070717; BR PI0508205 A 20070717; BR PI0508214 A 20070717; EP 1733071 A2 20061220; EP 1733072 A2 20061220;  
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WO 2005095670 A2 20051013; WO 2005095670 A3 20060504; WO 2005098086 A2 20051020; WO 2005098086 A3 20060504

DOCDB simple family (application)

**US 2005010693 W 20050324;** BR PI0508204 A 20050324; BR PI0508205 A 20050324; BR PI0508214 A 20050324; EP 05734780 A 20050324;  
EP 05760380 A 20050324; EP 05760434 A 20050324; JP 2007505281 A 20050324; JP 2007505282 A 20050324; JP 2007505283 A 20050324;  
KR 20067021947 A 20061023; KR 20067021948 A 20061023; KR 20067021949 A 20061023; TW 94121536 A 20050628;  
TW 94121537 A 20050628; TW 94121538 A 20050628; US 2005010691 W 20050324; US 2005010692 W 20050324